

U.S. Department of Commerce, Patent and Trademark	Atty. Docket No.	Application No.
INFORMATION DISCLOSURE STATEMENT BY APPLICANT	TNCR.152US5	10/070,079
	Applicant(s)	Conf. No.
(Use several sheets if necessary)	M. Vaez-Iravani et al.	7208
	Filing Date	Group
	January 9, 2004	2877

## U.S. Patent Documents

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
HP	AA	4,558,949	12/85	Uehara et al.			
HP	AB	4,893,932	1/1990	Knollenberg			
HP	AC	5,058,982	10/1991	Katzir			
	AD	5,389,794	2/14/1995	Allen et al.			
HP	AE	5,712,701	1/98	Dementi et al.			
HP	AF	5,929,983	7/99	Lu			
HP	AG	6,118,525	9/00	Fossey et al.			
HP	AH	6,169,601	1/01	Eremin et al.			

## U.S. Published Patent Application Documents

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate

## Foreign Patent Documents

							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
HP	AI	WO97/33158	9/1997	International			X	
HP	AJ	EP0624787	11/1994	Europe			Abstract	
HP	AK	DE4123916	1/1992	German			Abstract	
HP	AL	WO97/12226	4/1997	International			X	

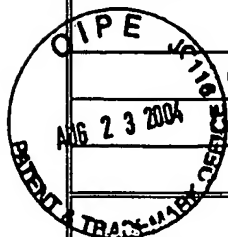
## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

HP	AM	"Surface Inspection System for Estimation of Wafer," Y. Yatsugake et al., <i>Hitachi Electronics Engineering Technical Report</i> , Vol. 11, January 1996, pp. 21-26
HP	AN	Figure, Hitachi Electronics Engineering Co., Ltd., presented by Etsuro Morita of Mitsubishi Materials Silicon Corp. in a presentation entitled "Exploration of COP and COP Defect Crystal Originated 'Particles'." at the 6 <sup>th</sup> International Workshop on 300 Millimeter Wafers on 12/5/1996 in Makuhari. Japan
HP	AO	Partial European Search Report dated October 18, 2000

Examiner <i>HP</i>	Date Considered <i>9/8/04</i>
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\*EXAMINER: initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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HP	AP	4,589,773	5/86	Ido et al.			
HP	AQ	4,740,079	04/88	Koizumi et al.			
HP	AR	4,966,457	10/90	Hayano et al.			
HP	AS	5,125,741	6/92	Okada et al.			
HP	AT	5,189,481	2/93	Jann et al.			
HP	AU	5,245,403	9/93	Kato et al.			
HP	AV	5,465,145	11/95	Nakashige et al.			

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*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
				None			

## Foreign Patent Documents

							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
HP	AW	WO96/15354	9/25/96	International			X	
HP	AX	WO97/04134	3/5/97	International			X	
HP	AY	WO99/14575	3/99	International			X	

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

HP	AZ	Search Report Corresponding to PCT Application No. PCT/US98/19564 issued by the International Patent Office on February 8, 1999.						

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